



## Notice of References Cited

Application No.

08/889,440

Examiner

Applicant(s)

Takeuchi et al.

Group Art Unit

			Н	ugh Jones	2763	P	age 1 of 1
			U.S. PATENT DOCUM	MENTS			
	DOCUMENT NO.	DATE		NAME CI		ASS	SUBCLASS
A	5,421,934	06/95		Misaka et al.		16	59
В	5,751,607	05/98		Ohta	30	64	578
С							
D							
E							
F							
G				-			
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J							
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			FOREIGN PATENT DOC	JMENTS	·		
	DOCUMENT NO.	DATE	COUNTRY	NAME	CL	ASS	SUBCLASS
N							
0							
Р							
a							
R							
s							
Т							
			NON-PATENT DOCUM	IENTS			
	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)						DATE
U	F. H. Baumann et al., "3D Modeling of Sputter and Reflow Processes for Interconnect Metals," IEDM 95, pg. 4.4.1-4.4.4						1995
v	T. Takagi, "Development of New Materials by Ionized-Cluster Beam Technique," Mat. Res. Soc. Symp. Proc. Vol. 27, pg. 501-511						1987
w	H. M. Jones et al., "Monte Carlo Investigation of Electron-Imapct Ionization in Liquid Xenon," Phys. Rev. B. vol. 48, pg. 9382-9387						1993
		<del></del>					

U. S. Patent and Trademark Office PTO-892 (Rev. 9-95)